L Number Hits Search Text  1 6 6734029.pn. or 6541354.pn.	
1 6 6 6734029.pn. or 6541354.pn.	or 6503570.pn. USPAT; 2004/08/12 13:53
or 6780465.pn. or 6646662.p	n. or US-PGPUB
6599582.pn. or 6518087.pn.	
2 6 6734029.pn. or 6541354.pn.	or 6503570.pn.   USPAT;   2004/08/12 13:53
or 6780465.pn. or 6646662.p	n. or US-PGPUB
6599582.pn. or 6518087.pn.	or
US20020114887	
7 6734029.pn. or 6541354.pn.	or 6503570.pn. USPAT; 2004/08/12 13:53
or 6780465.pn. or 6646662.p	
6599582.pn. or 6518087.pn.	or
"20020114887"	
40 (Furusawa.in. or Miyashita.	
Yudasaka.in. or Shimoda.in.	
Yokoyama.in. or Matsuki.in.	
Takeuchi.in. or JSR.as. or	(Seiko adj DERWENT;
Epson).as.) and ((silicon o	
(coat\$3 or film or layer or	deposit\$3))
and ((ring adj silane) or	cyclic adj
silane) or cyclosilane or o	
or Si5H10 or "Si.sub.5 H.su	
"Si.sub.5H.sub.10" or (cycl	o adj
pentasilane) or (cyclo adj	penta adj
- silane) or silylcyclopentas	
or "Si.sub.6H.sub.12" or "S	i.sub.6
H.sub.12" or (silyl near2	
cyclopentasilane))	
5 9 ((Furusawa.in. or Miyashita	in. or USPAT; 2004/08/12 14:10
Yudasaka.in. or Shimoda.in.	or US-PGPUB;
Yokoyama.in. or Matsuki.in.	or EPO; JPO;
Takeuchi.in. or JSR.as. or	
Epson).as.) and ((silicon o	
(coat\$3 or film or layer or	
and ((ring adj silane) or	
silane) or cyclosilane or o	
or Si5H10 or "Si.sub.5 H.su	
"Si.sub.5H.sub.10" or (cyc	o adj
pentasilane) or (cyclo adj	penta adj
silane) or silylcyclopentas	
or "Si.sub.6H.sub.12" or "S	1.Sub.6
H.sub.12" or (silyl near2	
cyclopentasilane))) and (inactive or pattern\$3 or se	logtive of
(\$4CVD or (vapor adj depos 6 2 (Furusawa.in. or Miyashita	
6 2 (Furusawa.in. or Miyashita Yudasaka.in. or Shimoda.in	
Yokoyama.in. or Matsuki.in	
Takeuchi.in. or JSR.as. or	
Epson).as.) and ((silicon o	
(coat\$3 or film or layer or	
and (active with inactive	
(vapor adj deposit\$3)))	(1000
7 1 (Furusawa.in. or Miyashita	in. or USPAT; 2004/08/12 14:1
Yudasaka.in. or Shimoda.in	,
Yokovama.in. or Matsuki.in	7-
Takeuchi.in. or JSR.as. or	
Epson).as.) and ((ring adj	
(cyclic adj silane) or cyc	
cyclopentasilane or Si5H10	or "Si.sub.5
H.sub.10" or "Si.sub.5H.su	o.10" or (cyclo
adj pentasilane) or (cyclo	
silane) or silylcyclopenta	silane or Si6H12
or "Si.sub.6H.sub.12" or "	Gi.sub.6
H.sub.12" or (silyl near2	
cyclopentasilane)) and (ac	rive with
inactive with (pattern\$3 o	region or
selectiv\$5 or \$4CVD or (va)	por adj
deposit\$3)))	]

				2004/00/12 14:06
8	31	((Furusawa.in. or Miyashita.in. or	USPAT;	2004/08/12 14:06
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
	,	Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
	}	Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
	1	Epson).as.) and ((silicon or Si) near2	IBM_TDB	
		(coat\$3 or film or layer or deposit\$3))		
		and ((ring adj silane) or (cyclic adj		
	1	silane) or cyclosilane or cyclopentasilane		
		or Si5H10 or "Si.sub.5 H.sub.10" or		
1		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6	,	
		H.sub.12" or (silyl near2		
		cyclopentasilane)) ) not (((Furusawa.in.		
}		or Miyashita.in. or Yudasaka.in. or		
		Shimoda.in. or Yokoyama.in. or Matsuki.in.		
		or Takeuchi.in. or JSR.as. or (Seiko adj		
		Epson).as.) and ((silicon or Si) near2		
		(coat\$3 or film or layer or deposit\$3))		
	1	and ((ring adj silane) or (cyclic adj		
1		silane) or cyclosilane or cyclopentasilane		
		or Si5H10 or "Si.sub.5 H.sub.10" or		
		-"Si-sub.5H-sub.10" or (cyclo-adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
	İ	cyclopentasilane)) ) and ((active or		
		inactive or pattern\$3 or selectiv\$4) near5	1	
		(\$4CVD or (vapor adj deposit\$3))))		
9	104	(Furusawa.in. or Miyashita.in. or	USPAT;	2004/08/12 14:13
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
		Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	1
		Epson).as.) and ((active or inactive or	IBM TDB	
		pattern\$3 or selectiv\$4) near5 (\$4CVD or	} _	
		(vapor adj deposit\$3)) with (Si or		
		silicon))		
11	0	1	USPAT;	2004/08/12 14:12
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
		Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
	1	Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and ((active or inactive or	IBM TDB	
		pattern\$3 or selectiv\$4) near5 (\$4CVD or	-	
		(vapor adj deposit\$3)) with (Si or		
1		silicon))) not ((Furusawa.in. or		
		Miyashita.in. or Yudasaka.in. or	,	
		Shimoda.in. or Yokoyama.in. or Matsuki.in.		
		or Takeuchi.in. or JSR.as. or (Seiko adj		
i		Epson).as.) and ((silicon or Si) near2		
1		(coat\$3 or film or layer or deposit\$3))		
1		and ((ring adj silane) or (cyclic adj		
		silane) or cyclosilane or cyclopentasilane		
		or Si5H10 or "Si.sub.5 H.sub.10" or		1
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		1
		H.sub.12" or (silyl near2		
		cyclopentasilane)))) and ((ring adj	ļ	
		silane) or (cyclic adj silane) or		
		cyclosilane or cyclopentasilane or Si5H10		
1		or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		1
	1	silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
1		H.sub.12" or (silyl near2 cyclopentasilane))	1	
			•	i

10	98	((Furusawa.in. or Miyashita.in. or	USPAT;	2004/08/12 14:12
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
		Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and ((active or inactive or	IBM TDB	
		pattern\$3 or selectiv\$4) near5 (\$4CVD or		
		(vapor adj deposit\$3)) with (Si or		
		silicon))) not ((Furusawa.in. or		ļ
		Miyashita.in. or Yudasaka.in. or		
		Shimoda.in. or Yokoyama.in. or Matsuki.in.		
		or Takeuchi.in. or JSR.as. or (Seiko adj		
		Epson).as.) and ((silicon or Si) near2		
		(coat\$3 or film or layer or deposit\$3))		
		and ((ring adj silane) or (cyclic adj		1
		silane) or cyclosilane or cyclopentasilane		
		or Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		ŀ
		pentasilane) or (cyclo adj penta adj		
	İ	silane) or silylcyclopentasilane or Si6H12		1
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane)))		
12	90	(Furusawa.in. or Miyashita.in. or	USPAT;	2004/08/12 14:13
		-Yudasaka in or Shimoda in or	-US-PGPUB;	
		Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and (((active with inactive)	IBM TDB	
		or pattern\$3 or selectiv\$4) near5 (\$4CVD	_	
		or (vapor adj deposit\$3)) with (Si or		
		silicon))		
13	84	((Furusawa.in. or Miyashita.in. or	USPAT;	2004/08/12 14:13
		Yudasaka.in. or Shimoda.in. or	US-PGPUB;	
		Yokoyama.in. or Matsuki.in. or	EPO; JPO;	
		Takeuchi.in. or JSR.as. or (Seiko adj	DERWENT;	
		Epson).as.) and (((active with inactive)	IBM TDB	
		or pattern\$3 or selectiv\$4) near5 (\$4CVD	1211_122	
		or (vapor adj deposit\$3)) with (Si or		
		silicon))) not ((Furusawa.in. or		
		Miyashita.in. or Yudasaka.in. or		
		Shimoda.in. or Yokoyama.in. or Matsuki.in.		
				l i
		or Takeuchi.in. or JSR.as. or (Seiko adj		
		Epson).as.) and ((silicon or Si) near2		
		(coat\$3 or film or layer or deposit\$3))		
		and ((ring adj silane) or (cyclic adj	1	
		silane) or cyclosilane or cyclopentasilane		
		or Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6	ľ	
		H.sub.12" or (silyl near2		
		cyclopentasilane)))		